



The **Xerox Research Centre of Canada** (XRCC) is Xerox's strategic materials research center, enabling the flow of leading-edge imaging materials from research concepts to supplies and consumables solutions. XRCC leverages its core competencies in materials design, synthesis, characterization, evaluation, and scale-up to deliver -- with partners -- environmentally sound materials and processes that support lower cost, higher quality color printing, as well as materials for new business creation.

The Xerox Research Centre of Canada is actively seeking a candidate at a Ph.D. level to join a progressive materials science group to contribute to exploratory research programs in the area of “marking materials applications”. We are interested in identifying suitable candidates in the area of (*but not limited to*) physical colloidal chemistry, interfacial science and self assembly.

A self-motivated individual would be responsible for the investigation and fundamental understanding of materials for nanotechnology applications. The individual will be expected to present findings at meetings and document them in internal reports and invention disclosures. Candidates should possess the following skill set:

- Proven knowledge of physical chemistry in colloidal interfacial science and self-assembly at a Ph.D. or Post Doctoral level is required.
- Experience in particle / nanoparticle characterization and modeling of supramolecular systems is desirable.
- Exposure to polymer synthesis, characterization and applications of polymeric and small molecule materials would be an asset.
- Ability to work well in a multidisciplinary team environment – a team player
- Communication, organization and presentation skills are essential

Xerox is actively committed to building a diversified workforce. If you are looking for a career that offers on-going challenge and growth, please email your resume to:

[HR@xrc.xerox.com](mailto:HR@xrc.xerox.com)

Website for Xerox Research Centre of Canada

<http://www.xerox.com/innovation/business-technology-research/enus.html>

*We thank everyone for their submission and interest but only those identified for an interview will be contacted.*